

Attorney Docket N . 040021-0306769  
Client Reference: OPP 031059 US

**PATENT**

**IN THE UNITED STATES PATENT AND TRADEMARK OFFICE**

In re application of: SEUNG-CHUL CHOI

Application No.:

Confirmation

No:

Filed: December 16, 2003

Group No.:

Examiner

For: CHEMICAL VAPOR DEPOSITION APPARATUS AND METHOD

Commissioner for Patents  
P.O. Box 1450  
Alexandria, VA 22313-1450

**APPLICATION DATA SHEET**  
**37 C.F.R. § 1.76**

**BIBLIOGRAPHIC DATA**

**1. Applicant information**

First applicant: SEUNG-CHUL CHOI  
Citizenship: Republic of Korea  
Residence: Seoul, Korea

**2. Correspondence information**

Correspondence for this application should be addressed as follows:

Customer No.: 00909

**3. Application information**

Title of Invention: CHEMICAL VAPOR DEPOSITION APPARATUS AND METHOD

Docket number assigned to this application: 040021-0306769

Suggested Classification: Class:

Subclass:

Technology Center to which subject matter is assigned:

Total number of drawing sheets: 3

Type of application:

Utility

Application is to be published. Suggested drawing figure for publication:

Secrecy order under § 5.2:

This application does not disclose subject matter of an application which is under a secrecy order pursuant to § 5.2.

**4. Representative information**

The following have a power of attorney or authorization of agent in this application:

Customer No.: 00909

**5. Foreign priority information**

Foreign priority is claimed for this application as follows:

Country: Republic of Korea  
Application No.: 10-2002-0080762  
Filing Date: December 17, 2002  
Status: Pending

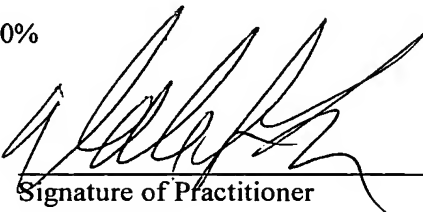
**6. Assignee information**

The assignee(s) of this application is/are:

Anam Semiconductor Inc.  
891-10 Daechi-dong, Kangnam-ku  
Seoul, 135-523  
KOREA  
Extent of interest of assignee in application: 100%

Date: December 16, 2003

Reg. No.: 28872  
Tel. No.: (703) 905-2126  
Customer No.: 00909



Signature of Practitioner  
Dale S. Lazar  
PILLSBURY WINTHROP LLP  
P.O. Box 10500  
McLean, VA 22102